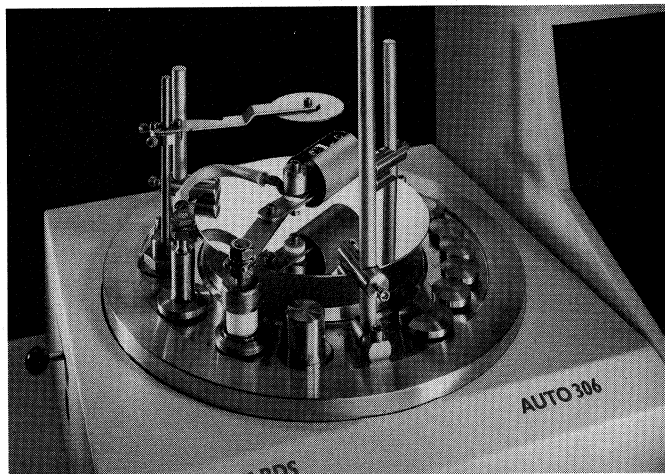


AUTO 306 RESISTANCE EVAPORATION SYSTEMS FOR RESEARCH AND DEVELOPMENT

Resistance evaporation

Resistance evaporation is often the most simple and cost-effective deposition technique. In this technique, most commonly used metals (such as aluminum, chromium, silver, gold and many others) are readily evaporated.

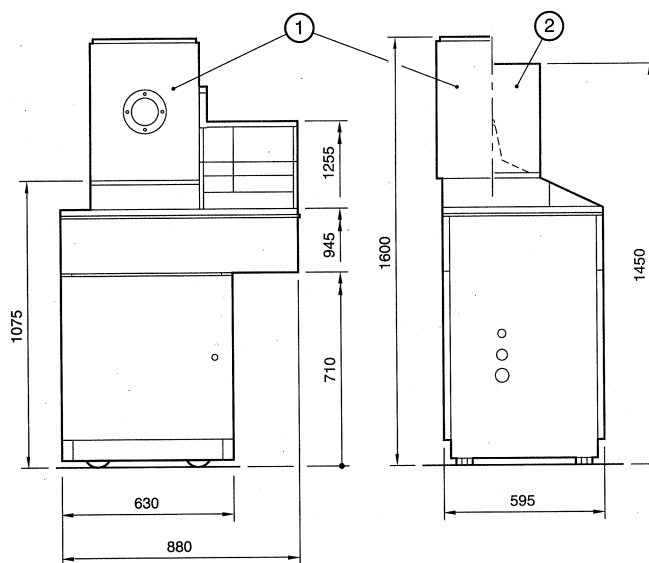
BOC Edwards Auto 306 resistance evaporation systems provide researchers with an affordable but capable tool that can be upgraded as required by adding more sophisticated deposition techniques.



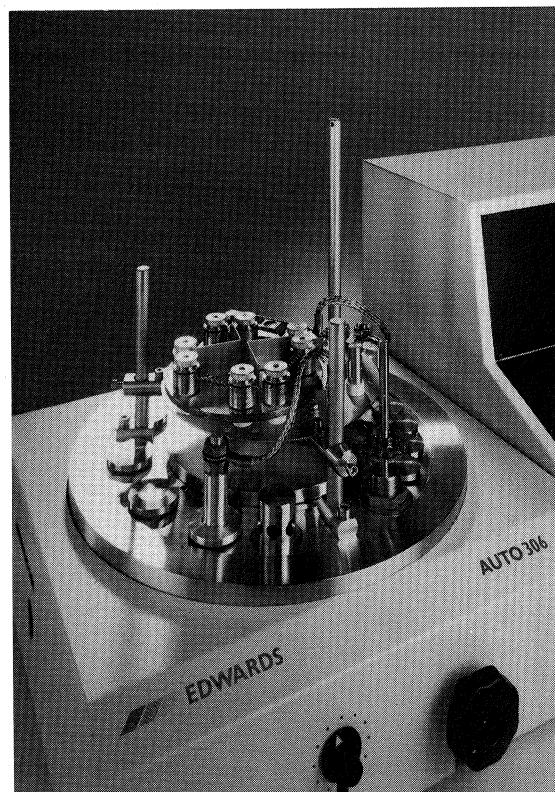
Resistance evaporation source for filament or boat evaporation. A built-in shield prevents unwanted coating of the vacuum chamber and adjacent deposition accessories.

Ultimate vacuum	
600 ls ⁻¹ diffusion pumped	2×10^{-7} mbar
350 ls ⁻¹ turbo pumped	7×10^{-7} mbar (no liquid N ₂ trap)
500 ls ⁻¹ turbo pumped	2×10^{-7} mbar
800 ls ⁻¹ cryo pumped	1×10^{-7} mbar
Liquid nitrogen trap capacity*	1.4 l
Pump oil/ fluid capacity	
RV12 rotary pump	750 ml, Ultragrade 19
E04/160K diffusion pump	175 ml, Santovac 5
Weight (approximate)	200 kg
Electrical supply	240 or 220 V 1 ph 50 Hz or 210 V 1 ph 60 Hz
Electrical supply cable	2 m x 3 wire
Maximum power consumption	3 kVA
Enclosure rating	IP20
Cooling water flowrate	1.2 lmin ⁻¹ at 20 °C
Pumpdown time	
Time to 10 ⁻⁵ mbar	4 minutes
Time to 10 ⁻⁶ mbar	25 minutes
Tested leak rate	$\leq 10^{-9}$ mbar ls ⁻¹

* Trap fitted to diffusion pumped and 500 ls⁻¹ turbo pumped versions only.



- 1 With FL400 chamber
- 2 With Glass chamber



Four position turret evaporation source capable of sequentially depositing up to 4 different metals without breaking vacuum. Sources are selected and rotated into the evaporation position using a simple handwheel control. The sources can be configured to evaporate from the center or the side of the vacuum chamber for optimum film thickness uniformity onto a choice of static or rotating substrate fixtures.